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Reg. No.	:	••••	••••	••••	 ••••	
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Third Semester M.Sc. Degree Examination, March 2022 Physics

Special Paper I

PH 233 M: MATERIALS SCIENCE I

(2020 Admission)

Time: 3 Hours Max. Marks: 75

PART – A

Answer **any five** questions. Each question carries **3** marks.

- 1. Briefly discuss dislocations in crystals.
- 2. Differentiate weak excitonic confinement and strong excitonic confinement.
- 3. What are the capabilities that an equipment associated with thermal Chemical vapour deposition (CVD) process should have?
- 4. Differentiate between heterogeneous and homogeneous nucleation.
- 5. What you mean by Ellipsometry?
- 6. How can you express the thickness variation on a coated surface using the variation in deposition?
- 7. What is the difference between nucleation and crystal growth?
- 8. What are high vacuum pumps?

 $(5 \times 3 = 15 \text{ Marks})$

PART - B

Answer three questions. Each carries 15 marks.

- 9. (a) Give a brief note on types of imperfections in crystals.
 - (b) Discuss the significance of Line Kronger Vink notation.

OR

- 10. (a) Derive Fick's second law of Diffusion.
 - (b) What are the applications of diffusion?
- 11. (a) Discuss Epitaxy.
 - (b) Discuss the theories of epitaxial growth.

OR

- 12. What do you mean by nucleation? Discuss heterogeneous formation of 3D nuclei. Also express the rate of nucleation.
- 13. (a) With a neat diagram explain Sputter Deposition.
 - (b) Give a note on common types of sputter sources.

OR

- 14. (a) How electroplating is done? What are the requisites for successful electroplating?
 - (b) What are the advantages and disadvantages of electroplating technique?

 $(3 \times 15 = 45 \text{ Marks})$

PART - C

Answer any three questions. Each carries 5 marks.

15. In diffusion of dopant atoms from a continuous source (C₀) into semiconductor wafer was carried out for time t₁ and diffusivity D₁. This was followed by a second drive in diffusion time t₂ with diffusivity D₂. Show that the resulting dopant concentration profile is given by $C(x, t) = \frac{2C_0}{\pi} \sqrt{\frac{D_1 t_1}{D_2 t_2}} \exp{-\frac{x^2}{4D_2 t_2}}$

If the drive in diffusion is essentially that form an instantaneous surface source.

- 16. A steel rod has uniform concentration of 0.25wt% carbon. One end of the rod is kept in contact with an atmosphere of carbon concentration of 1.20wt%. The rod is heated to 950°C. How long will it take to get a concentration of 0.7% at depth of 0.5 mm? Diffusion coefficient of carbon in steel at 950°C is 1.6 × 10⁻¹¹ m²/s.
- 17. Using suitable diagram, explain Czochralski method of crystal growth. Mention its advantages and disadvantages.
- 18. What is the mass percentage of sodium hydroxide in a solution that is made by dissolving 8.00g NaOH in 50.0g H₂O? Will the solution be saturated or unsaturated at 20°C?
- 19. The vacancy migration energy in copper is 0.8 eV. The self-diffusion coefficient at 700K and 1000K are $3.43 \times 10^{-15} \text{m}^2/\text{s}$ and $1.65 \times 10^{-11} \text{ m}^2/\text{s}$. Determine vacancy concentration at these two temperatures.
- 20. Briefly explain two step theory of crystal growth with mathematical support.

 $(3 \times 5 = 15 \text{ Marks})$

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